

U.S. Department of Commerce, Patent and Trademark Office					Atty Docket No.		Serial No.	
					M-15230 US		10/632,154	
INFORMATION DISCLOSURE STATEMENT BY APPLICANT (Use several sheets if necessary)					Applicant			
					Yi Ding			
APR 20 2004					Filing Date		Group	
					July 30, 2003		Unassigned 2823	
U.S. Patent Documents								
*Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate	
KN	AA	6,420,231	16 Jul. 2002	Harari et al.				
KN	AB	2003/0218908 A1	27 Nov. 2003	Park et al.				
KN	AC	2004/0004863 A1	8 Jan. 2004	Wang				
	AD							
	AE							
	AF							
	AG							
	AH							
Foreign Patent Documents								
							Translation	
		Document	Date	Country	Class	Subclass	Yes	No
KN	AI	EP 0 938 098 A2	25 Aug. 1999	Europe				
	AJ							
	AK							
	AL							
OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)								
KN	AM	United States Patent Application No. 10/798,475, entitled "Fabrication of Conductive Lines Interconnecting Conductive Gates in Nonvolatile Memories and Non-Volatile Memory Structures," Filed on March 10, 2004; Attorney Docket No. M-15296 US.						
KN	AN	United States Patent Application No. 10/797,972, entitled "Fabrication of Conductive Lines Interconnecting First Conductive Gates in Nonvolatile Memories Having Second Conductive Gates Provided By Conductive Gates Lines, Wherein The Adjacent Conductive Gate Lines For The Adjacent Columns Are Spaced From Each Other; And Non-Volatile Memory Structures," Filed on March 10, 2004; Attorney Docket No. M-15297 US.						
	AO							
	AP							
Examiner		Date Considered						
J. Huenguyen		07/23/04						
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)		
KN	AR	Van Duuren, Michiel et al., "Compact poly-CMP Embedded Flash Memory Cells For One or Two Bit Storage," Philips Research Leuven, Kapeldreef 75, B3001 Leuven, Belgium, pages 73-74.
KN	AS	United States Patent Application No. 10/440,466, entitled "Fabrication Of Conductive Gates For Nonvolatile Memories From Layers With Protruding Portions," Filed on May 16, 2003; Attorney Docket No.: M-12979 US.
KN	AT	United States Patent Application No. 10/440,005, entitled "Fabrication of Dielectric On A Gate Surface To Insulate The Gate From Another Element Of An Integrated Circuit," Filed on May 16, 2003; Attorney Docket No.: M-15203 US.
KN	AU	United States Patent Application No. 10/440,508, entitled "Fabrication Of Gate Dielectric In Nonvolatile Memories Having Select, Floating And Control Gates," Filed on May 16, 2003; Attorney Docket No.: M-15204 US.

Examiner <i>KP</i>	Date Considered <i>07/23/04</i>
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OTHER ART (Including Author, Title, Date, Pertinent Pages, Etc.)			
KN	AV	United States Patent Application No. 10/440,500, entitled "Integrated Circuits With Openings that Allow Electrical Contact To Conductive Features Having Self-Aligned Edges," Filed on May 16, 2003; Attorney Docket No.: M-15205 US.	
KN	AW	United States Patent Application No. 10/393,212, entitled "Nonvolatile Memories And Methods Of Fabrication," Filed on March 19, 2003; Attorney Docket No.: M-12902 US.	
KN	AX	United States Patent Application No. 10/411,813, entitled "Nonvolatile Memories With A Floating Gate Having An Upward Protrusion," Filed on April 10, 2003; Attorney Docket No.: M-12903 US.	
KN	AY	United States Patent Application No. 10/393,202, entitled "Fabrication of Integrated Circuit Elements In Structures With Protruding Features," Filed on March 19, 2003; Attorney Docket No.: M-15151 US.	
KN	AZ	United States Patent Application No. 10/631,941, entitled "Nonvolatile Memory Cell With Multiple Floating Gates Formed After The Select Gate," Filed on July 30, 2003; Attorney Docket No.: M-15171 US.	
KN	BA	United States Patent Application No. 10/632,155, entitled "Nonvolatile Memory Cells With Buried Channel Transistors," Filed on July 30, 2003; Attorney Docket No.: M-15222 US.	
KN	BB	United States Patent Application No. 10/632,007, entitled "Arrays Of Nonvolatile Memory Cells Wherin Each Cell Has Two Conductive Floating Gates," Filed on July 30, 2003; Attorney Docket No.: M-15223 US.	
KN	BC	United States Patent Application No. 10/631,452, entitled "Fabrication Of Dielectric For A Nonvolatile Memory Cell Having Multiple Floating Gates," Filed on July 30, 2003; Attorney Docket No.: M-15229 US.	
KN	BD	United States Patent Application No. 10/631,552, entitled "Nonvolatile Memories And Methods Of Fabrication," Filed on July 30, 2003; Attorney Docket No.: M-12902-1P US.	
KN	BE	United States Patent Application No. 10/632,186, entitled "Nonvolatile Memory Cell With Multiple Floating Gates Formed After The Select Gate And Having Upward Protrusions," Filed on July 30, 2003; Attorney Docket No.: M-15241 US.	
	BF		
	BG		
	BH		
Examiner <i>K. P. Chien</i>		Date Considered 07/23/04	
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K.N.	AI	6,326,661	4 Dec. 2001	Dormans et al.			
K.N.	AJ	6,355,524	12 Mar. 2002	Tuan et al.			
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K.N.	AL	Shirota, Riichiro "A Review of 256Mbit NAND Flash Memories and NAND Flash Future Trend," February 2000, Nonvolatile Memory Workshop in Monterey, California, pages 22-31.					
K.N.	AM	Naruke, K.; Yamada, S.; Obi, E.; Taguchi, S.; and Wada, M. "A New Flash-Erase EEPROM Cell with A Sidewall Select-Gate On Its Source Side," 1989 IEEE, pages 604-606.					
K.N.	AN	Wu, A.T.; Chan T.Y.; Ko, P.K.; and Hu, C. "A Novel High-Speed, 5-Volt Programming EPROM Structure With Source-Side Injection," 1986 IEEE, 584-587.					
K.N.	AO	Mizutani, Yoshihisa; and Makita, Koji "A New EPROM Cell With A Sidewall Floating Gate Fro High-Density and High Performance Device," 1985 IEEE, 635-638.					
K.N.	AP	Ma, Y.; Pang, C.S.; Pathak, J.; Tsao, S.C.; Chang, C.F.; Yamauchi, Y.; Yoshimi, M. "A Novel High Density Contactless Flash Memory Array Using Split-Gate Source-Side-Injection Cell for 5V-Only Applications," 1994 Symposium on VLSI Technology Digest of Technical Papers, pages 49-50.					
K.N.	AQ	Mih, Rebecca et al. "0.18um Modular Triple Self-Aligned Embedded Split-Gate Flash Memory," 2000 Symposium on VLSI Technology Digest of Technical Papers, pages 120-121.					
K.N.	AR	Ma, Yale et al., "A Dual-Bit Split-Gate EEPROM (DSG) Cell in Contactless Array for Single Vcc High Density Flash Memories," 1994 IEEE, 3.5.1-3.5.4.					
Examiner		Date Considered					
J. H. Hengstenberg		07/23/04					
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U.S. Patent Documents

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KN	AT	6,438,036	20 Aug. 2002	Seki et al.			
KN	AU	6,486,023	26 Nov. 2002	Nagata			
KN	AV	6,541,324	1 Apr. 2003	Wang			
KN	AW	2002/0064071 A1	30 May 2002	Takahashi et al.			
KN	AX	2002/0197888 A1	26 Dec. 2002	Huang et al.			
KN	AY	6,266,278	24 Jul. 2001	Harari et al.			
KN	AZ	5,901,084	4 May 1999	Ohnakado			
KN	BA	6,518,618	11 Feb. 2003	Fazio et al.			
KN	BB	6,541,829	1 Apr. 2003	Nishinohara et al.			
KN	BC	6,414,872	2 Jul. 2002	Bergemont et al.			

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KN	BD	Spinelli, Alessandro S., "Quantum-Mechanical 2D Simulation of Surface-and Buried-Channel p-MOS," 2000 International Conference on Simulation of Semiconductor Processes and Devices: SISPAD 2000, Seattle, WA September 6-8, 2000
KN	BE	Kim, K.S. et al. "A Novel Dual String NOR (DuSnor) Memory Cell Technology Scalable to the 256 Mbit and 1 Gbit Flash Memories," 1995 IEEE 11.1.1-11.1.4
KN	BF	Bergemont, A. et al. "NOR Virtual Ground (NVG)- A New Scaling Concept for Very High Density FLASH EEPROM and its Implementation in a 0.5 um Process," 1993 IEEE 2.2.1-2.2.4
KN	BG	Van Duuren, Michiel et al., "Compact poly-CMP Embedded Flash Memory Cells For One or Two Bit Storage," Philips Research Leuven, Kapeldreef 75, B3001 Leuven, Belgium, pages 73-74.
Y	BH	
	BI	
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Examiner

Khienquyn

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